Supplementary Data

1. Images of seeding arrays

1.1 Seeds from electron beam lithography method (scale bar = 250 nm)

The CuPc material was removed from the seeds in order to acquire this image. Some residue remains, but the periodicity of the seeds is evident.

1.2 Seeds from block copolymer method (scale bar = 250 nm)
2. Images used for column density calculation

2.1 CuPc on bare Si substrate, $\alpha = 85^\circ$
2.2 CuPc on block copolymer seeded Si substrate, $\alpha = 85^\circ$
2.3 CuPc on bare Si substrate, $\alpha = 80^\circ$
2.4 CuPc on block copolymer seeded Si substrate, $\alpha = 80^\circ$
2.5 ZnPc on bare Si substrate, $\alpha = 80^\circ$
2.6 ZnPc on block copolymer seeded Si substrate, $\alpha = 80^\circ$